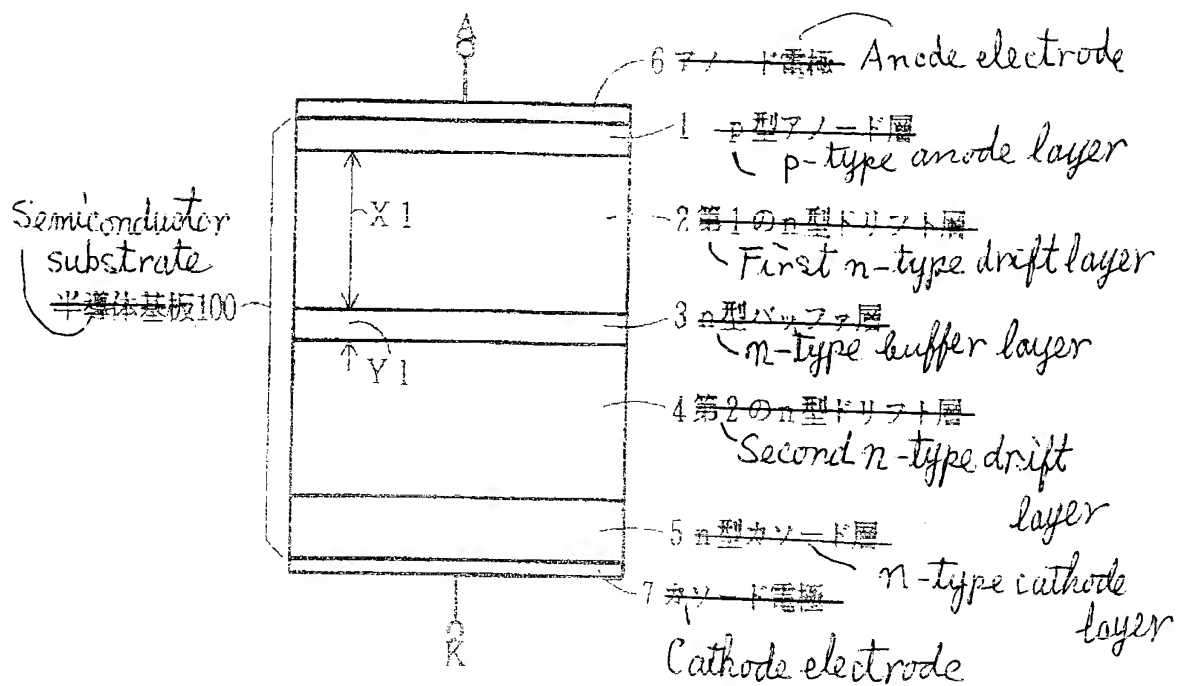


Fig. 1



【図2】

Fig. 2

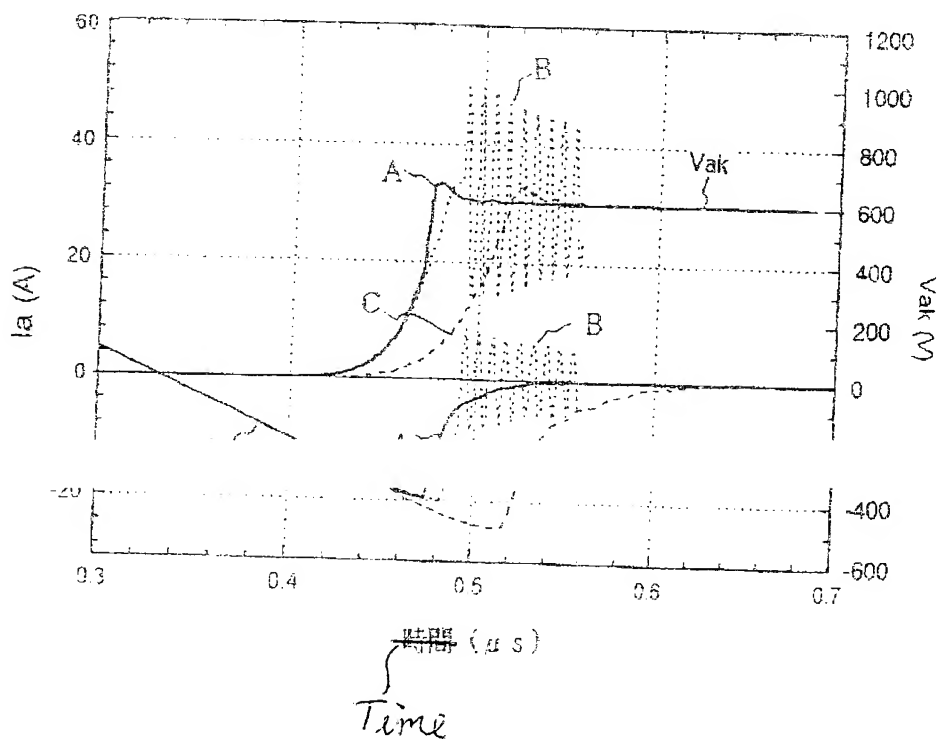


Fig. 3(a)

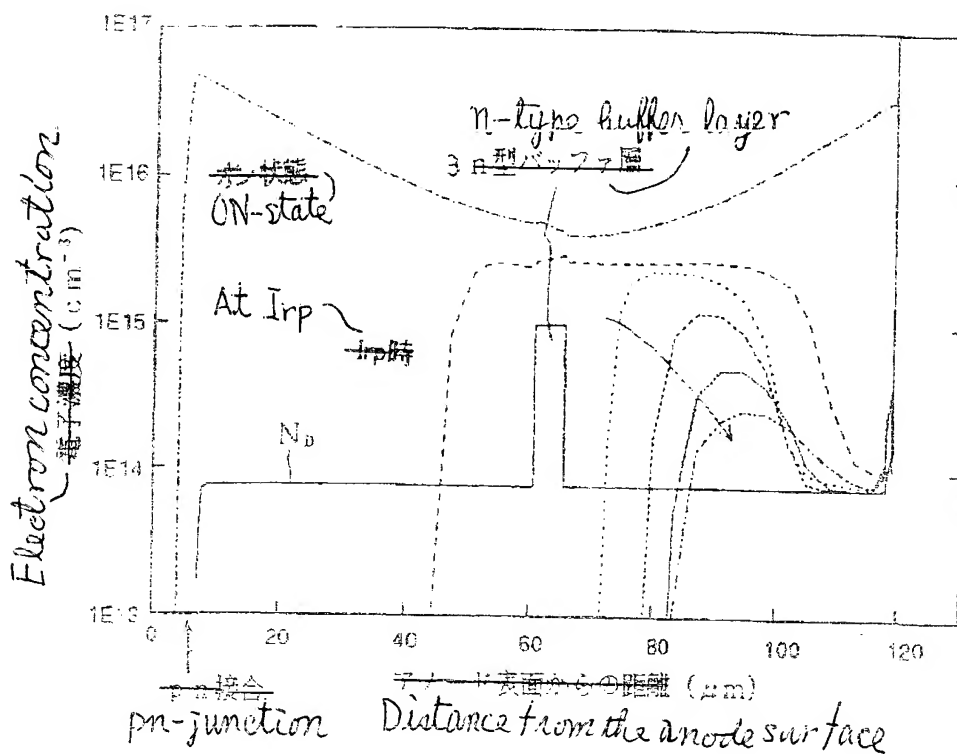


Fig. 3(b)

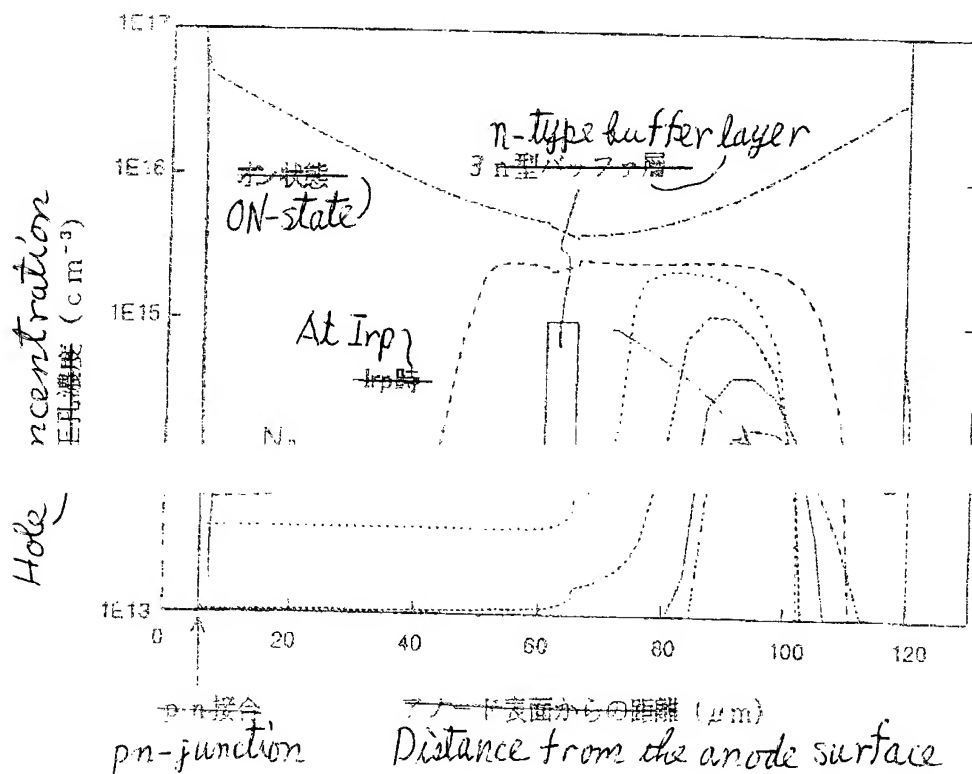


Fig. 4(a)

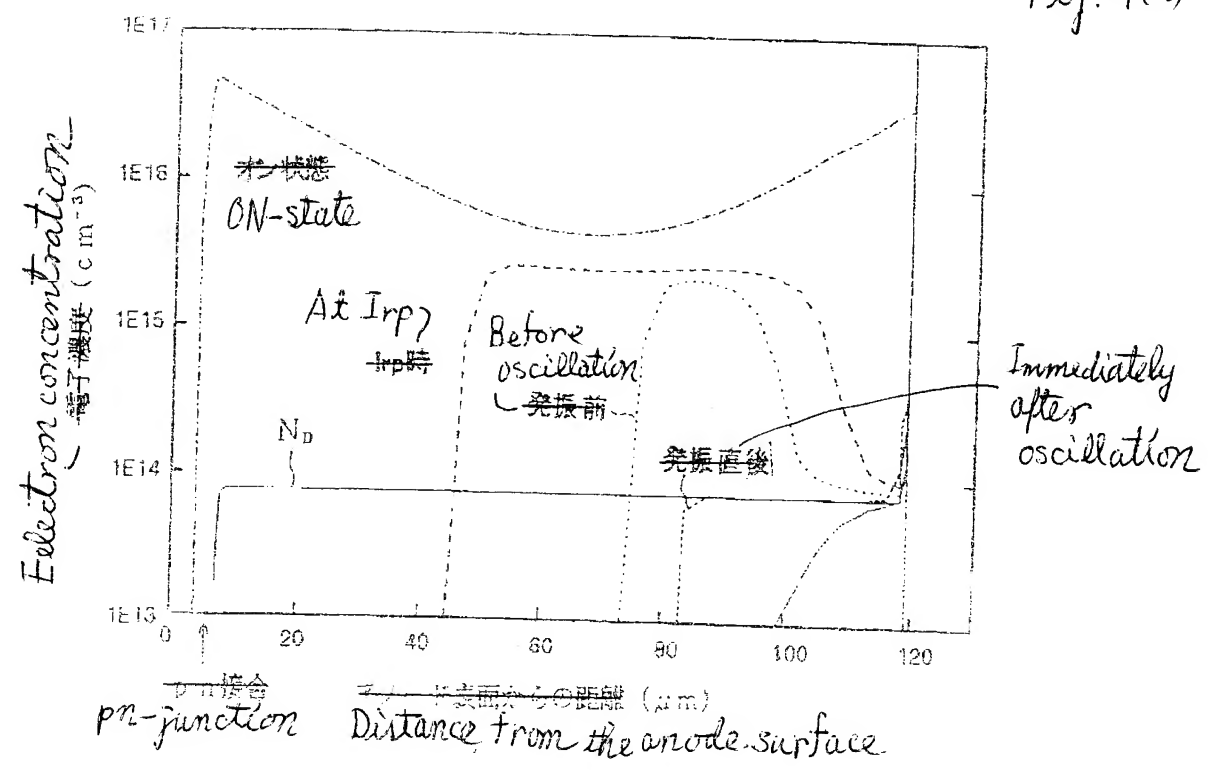


Fig. 4(b)

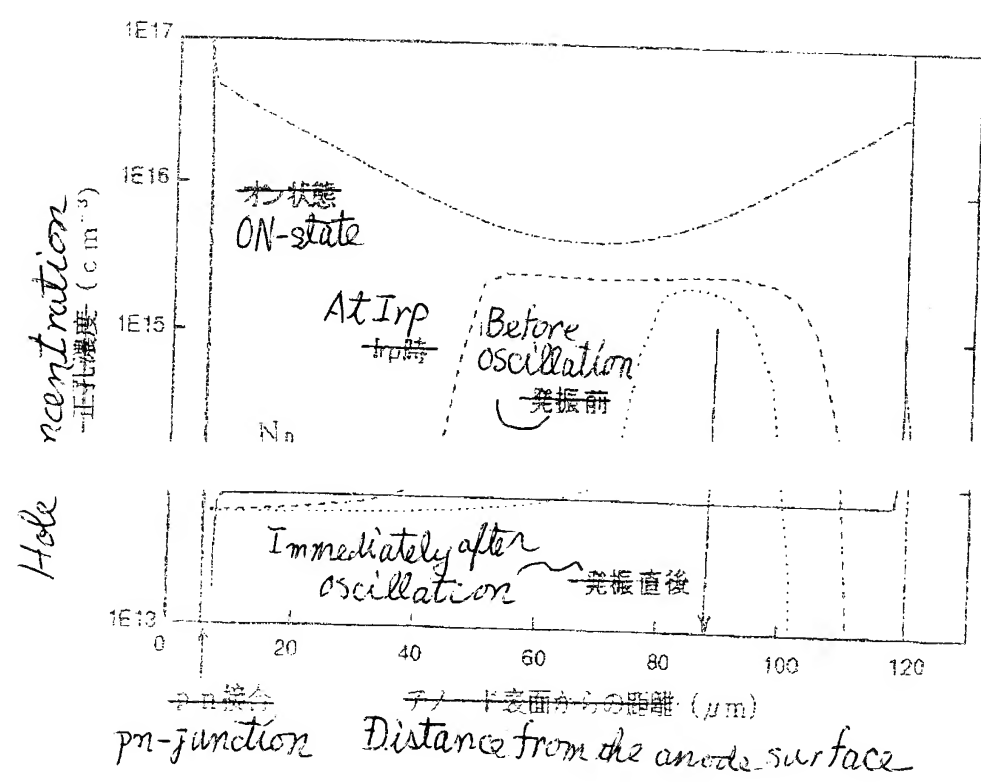


Fig. 5

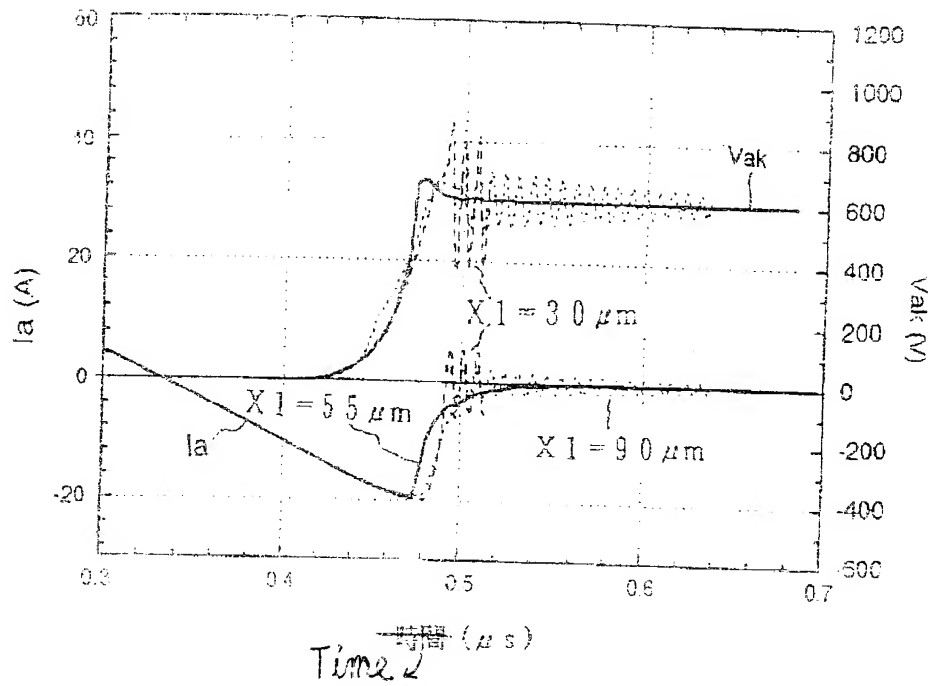


Fig. 6

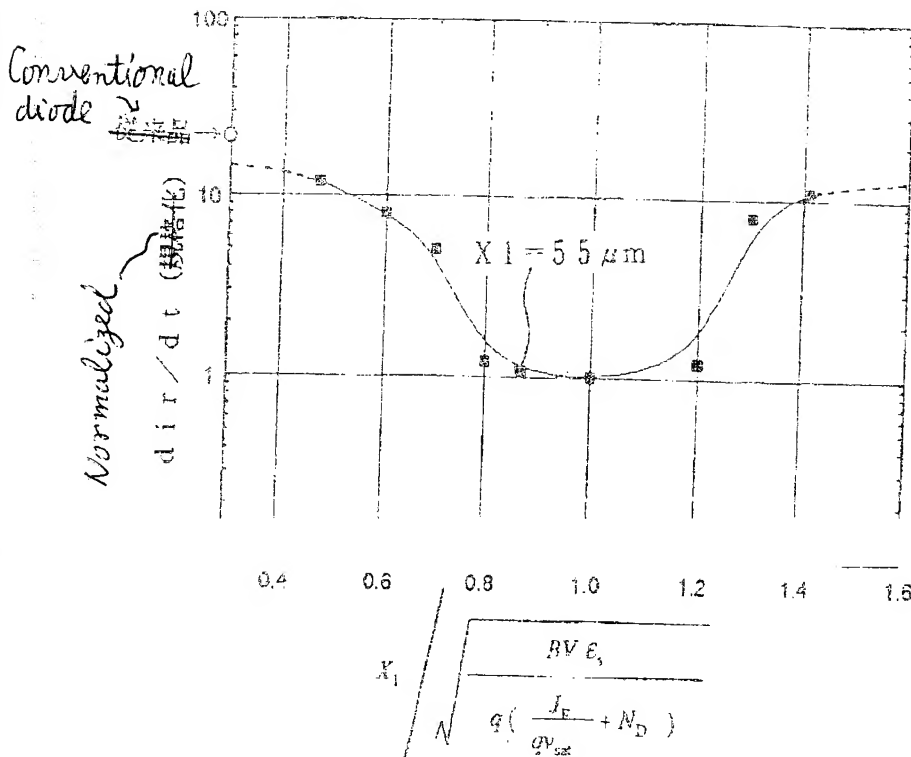


Fig. 7

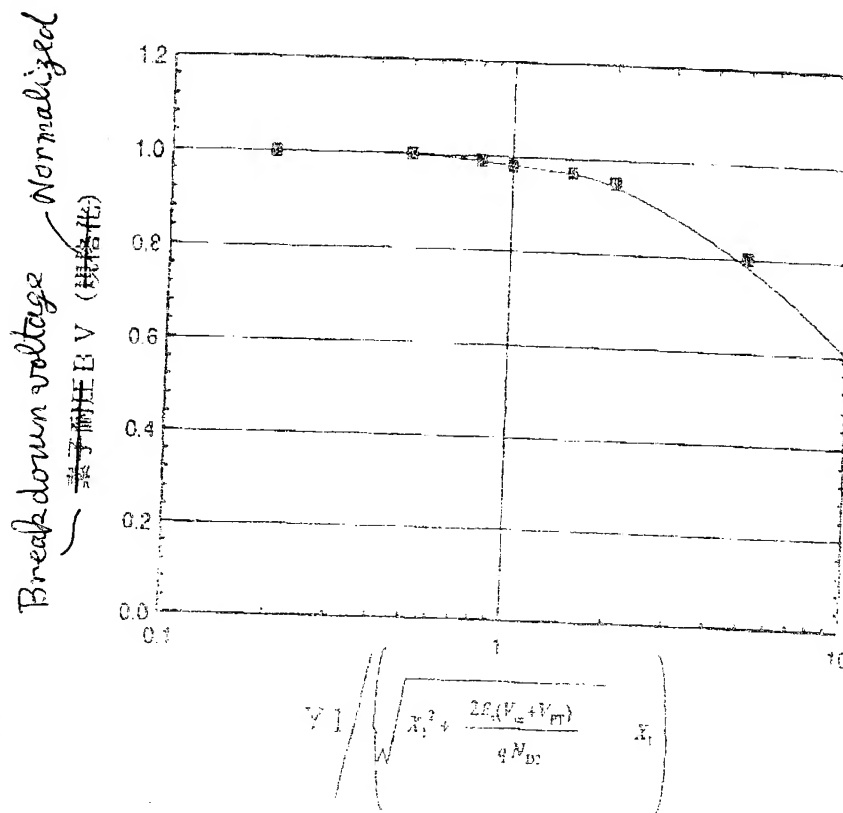


Fig. 8

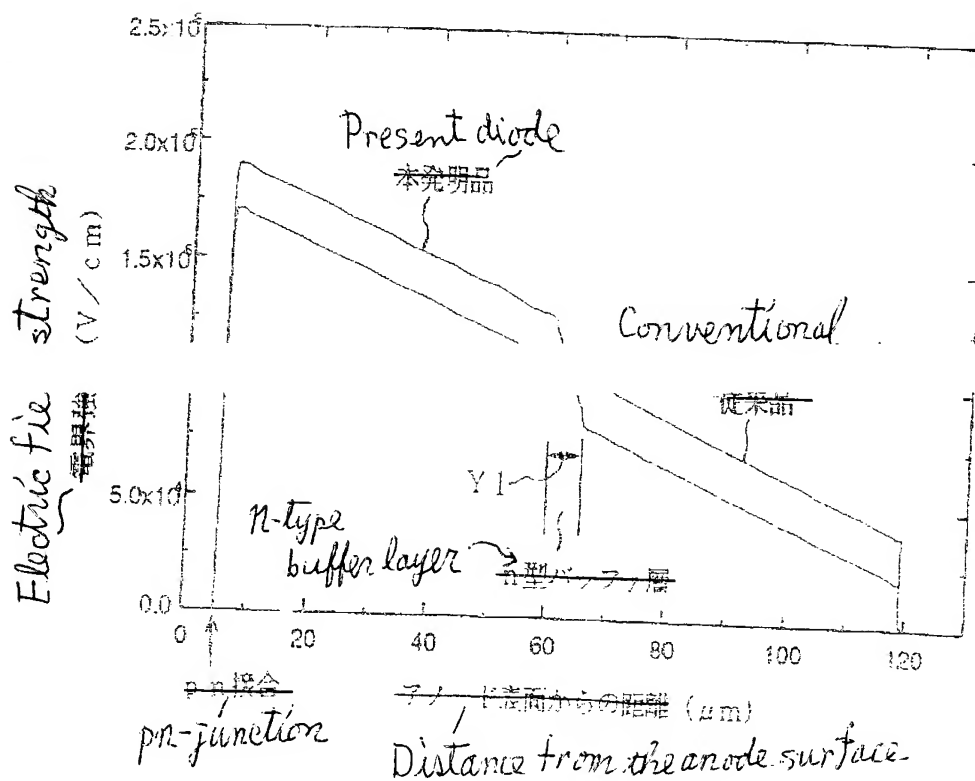


Fig. 9

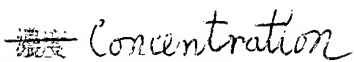
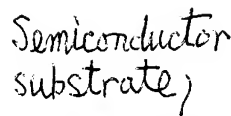
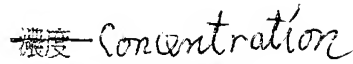


Fig. 10



~~半導體基板100~~

Fig. 11(b)



Second n-type buffer region  
(lightly doped)



Fig. 12(b)

Fig. 13(a)

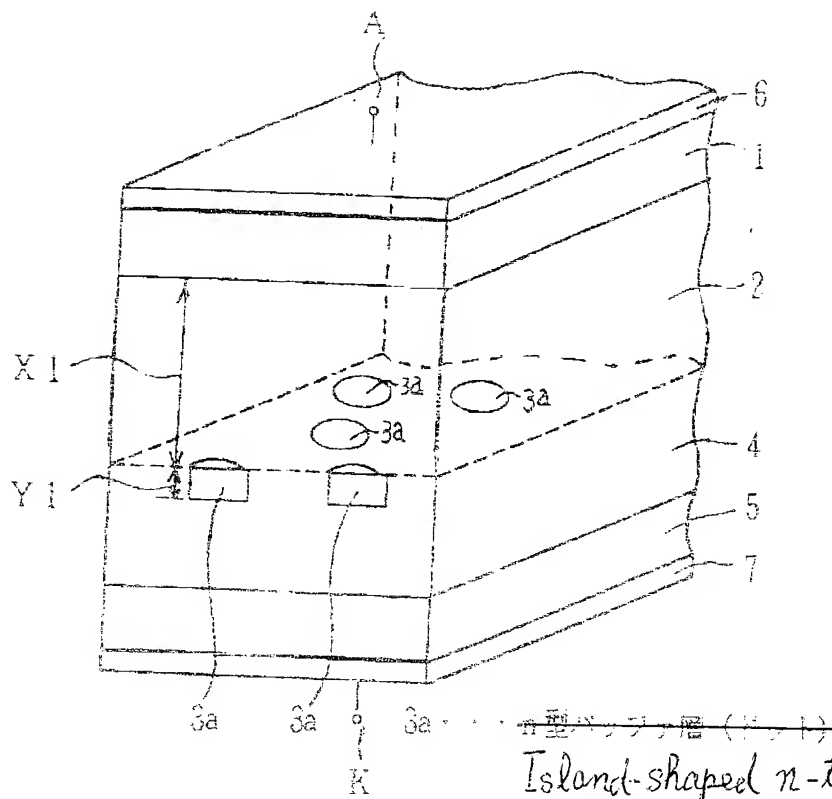


Fig. 13(b)

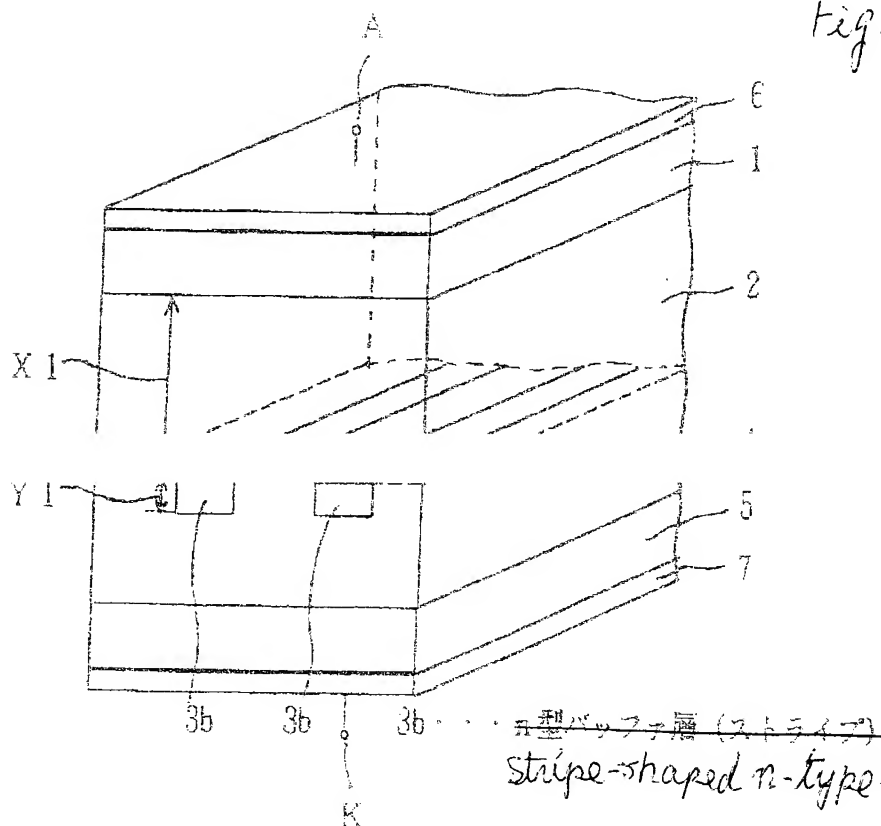
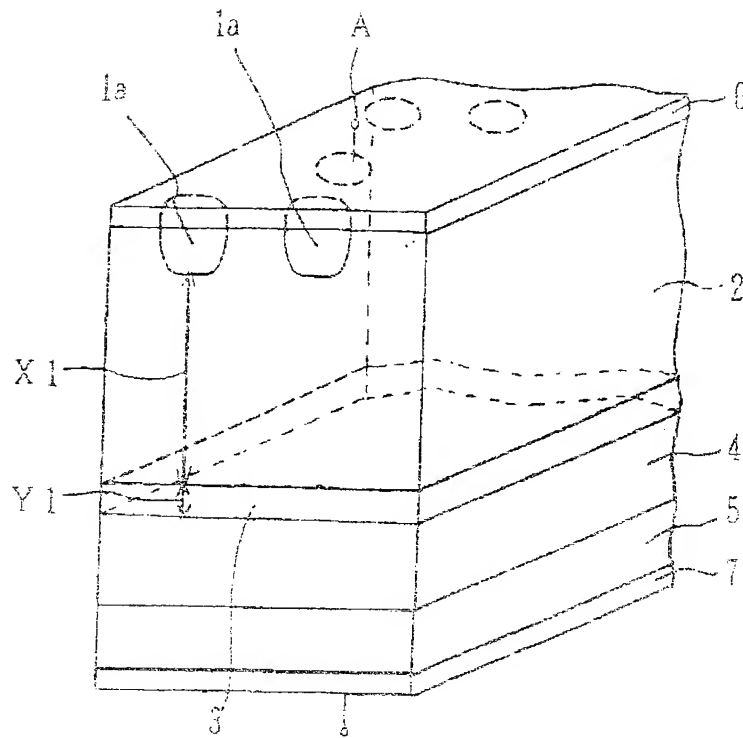




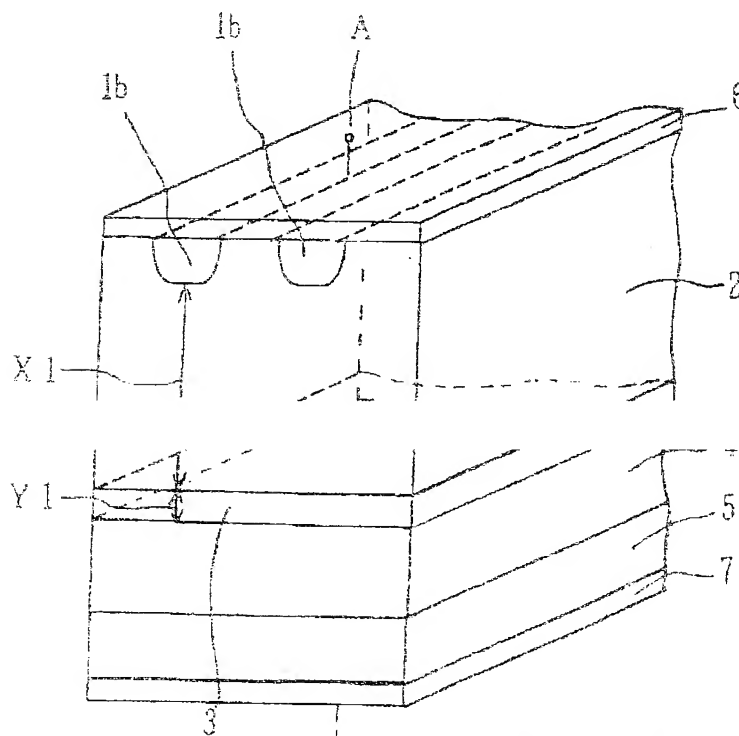
Fig. 14(a)



1a . . . p型アノード層 (アイランド)  
 K

Island-shaped p-type anode region

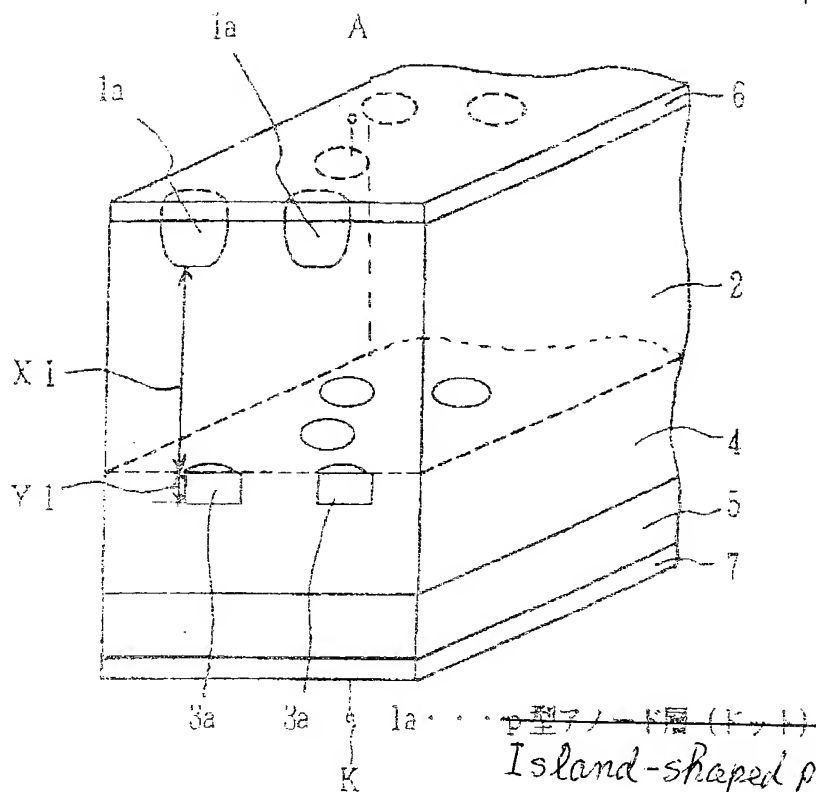
Fig. 14(b)



1b . . . p型アノード層 (ストライプ)  
 K

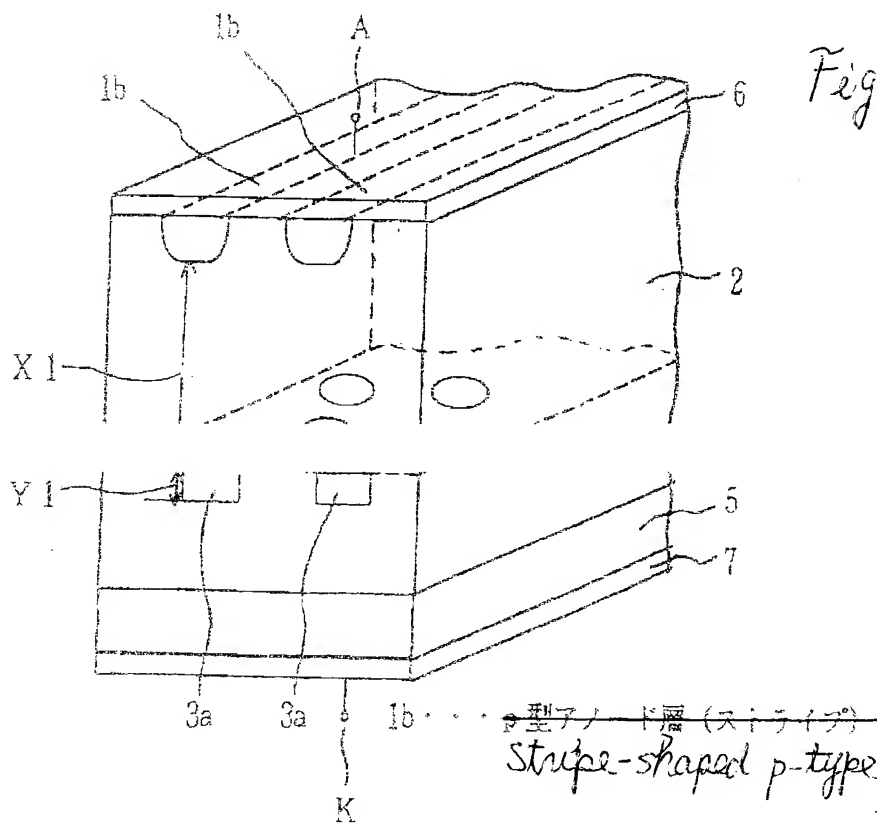
Stripe-shaped p-type anode region

Fig. 15(a)



Island-shaped p-type anode region

Fig. 15(b)



Stripe-shaped p-type anode region

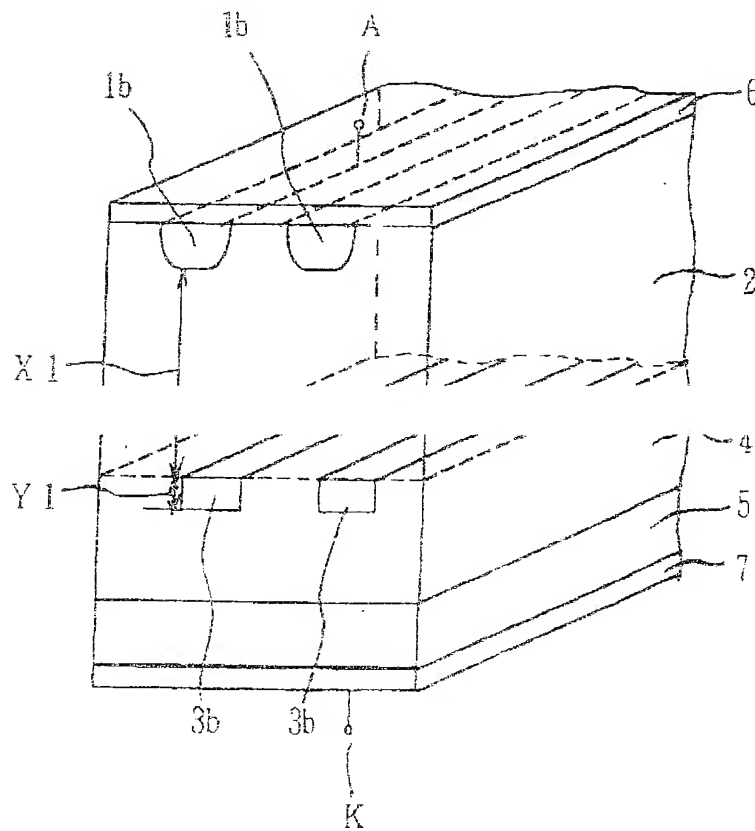
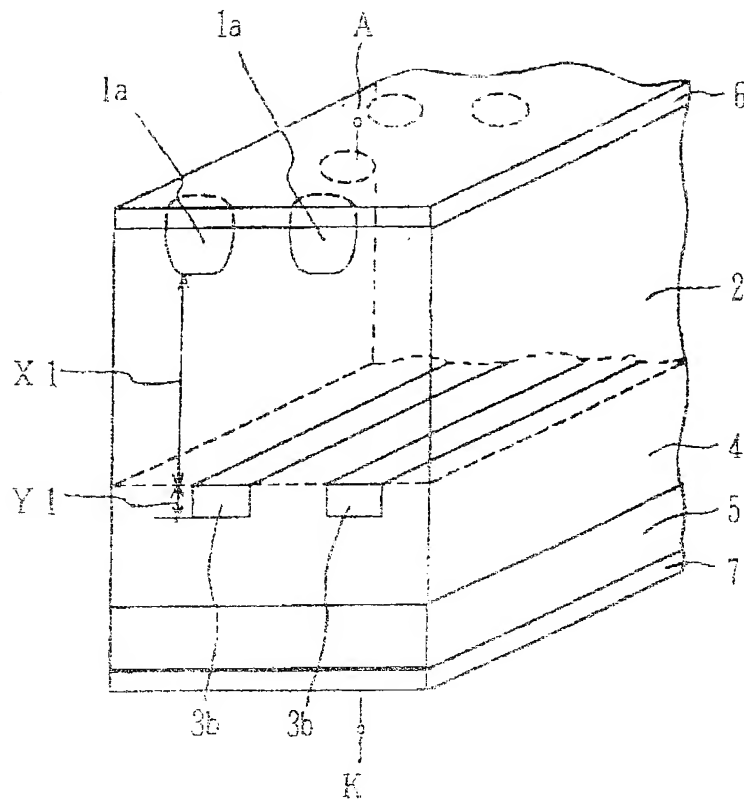




Fig. 19(a)

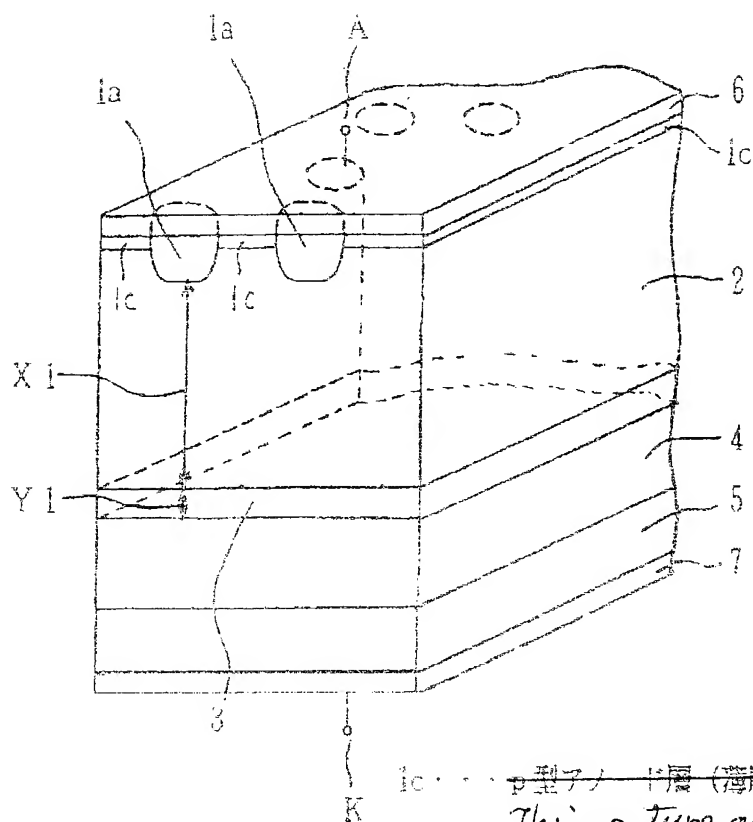


Fig. 19(b)

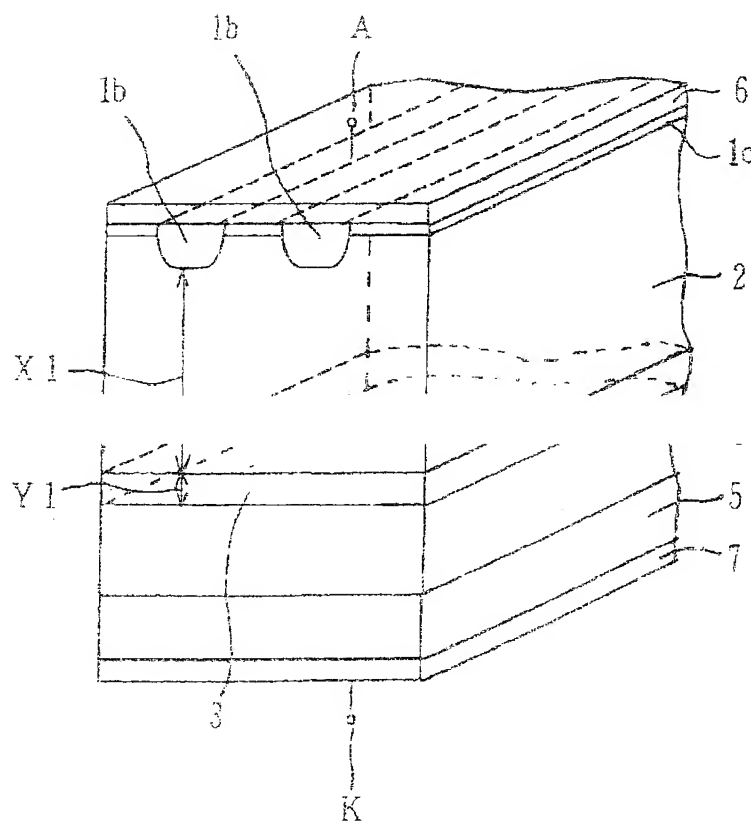


Fig. 20(a)

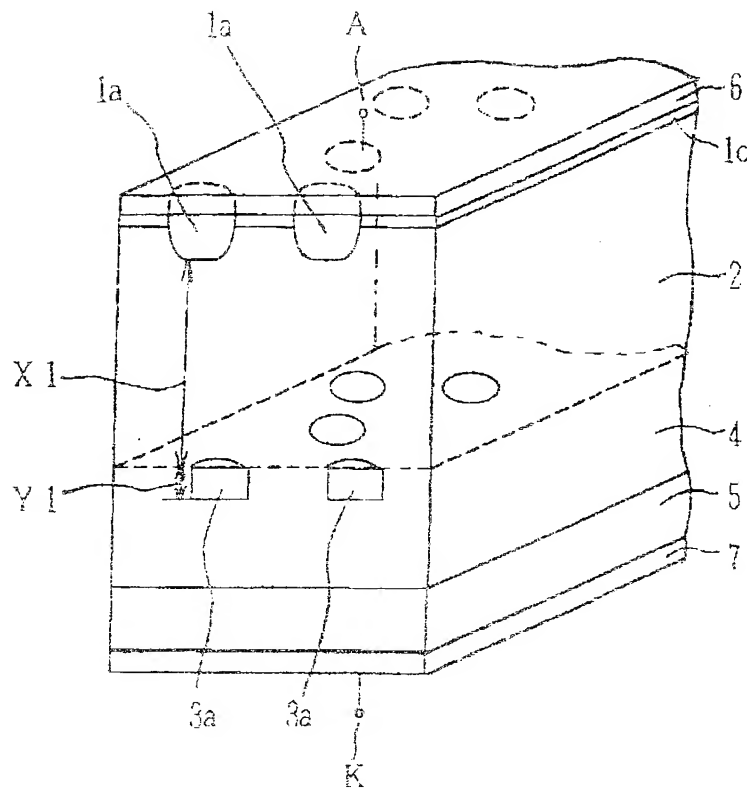


Fig. 20(b)

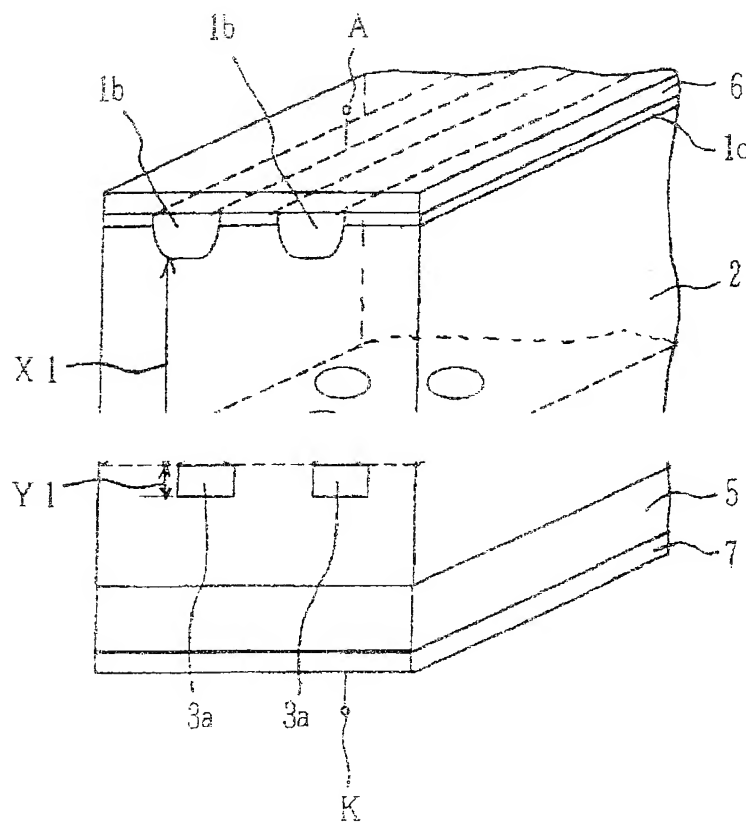


Fig. 21

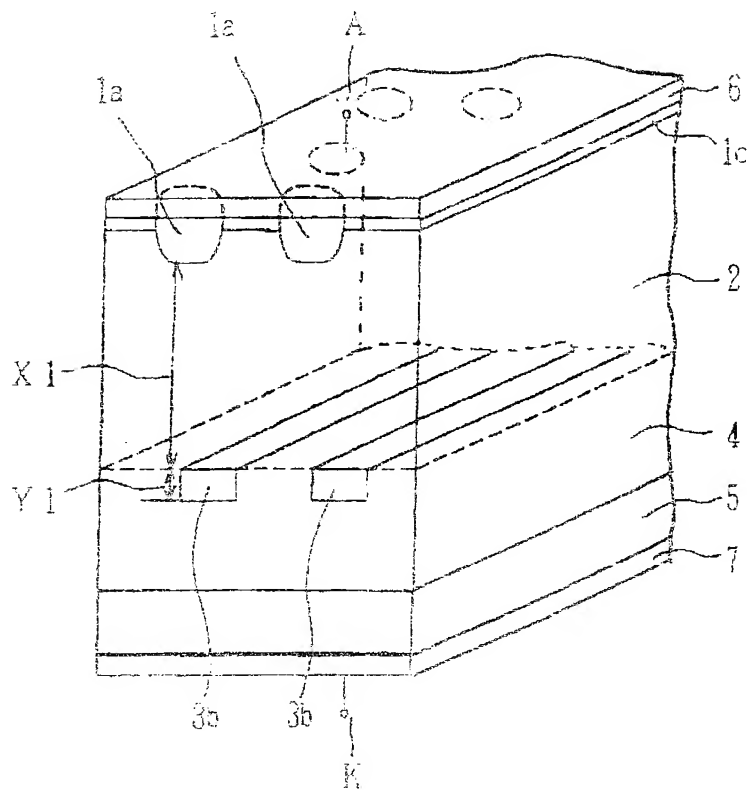


Fig. 22

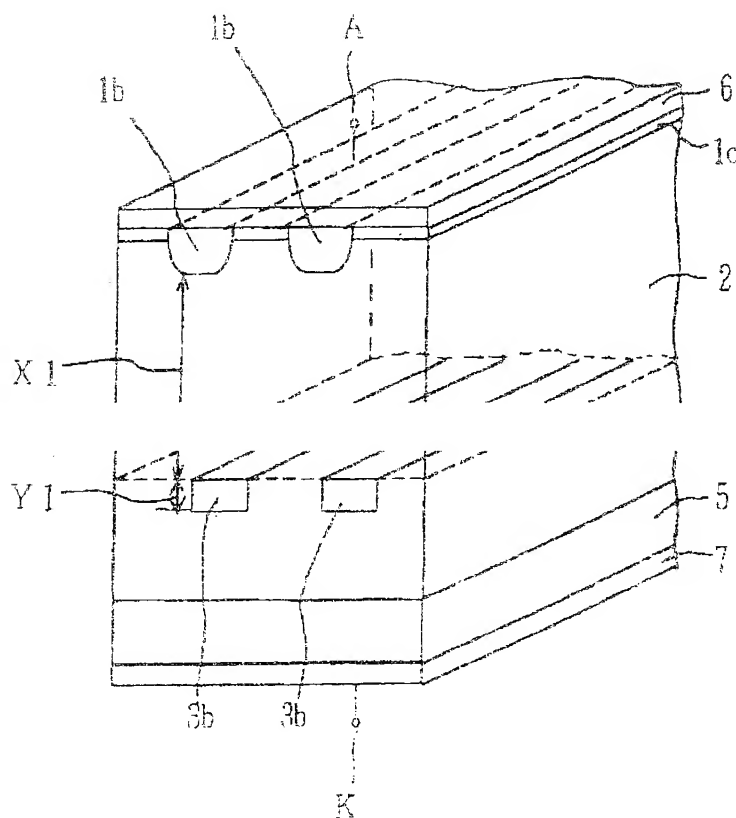


Fig. 23

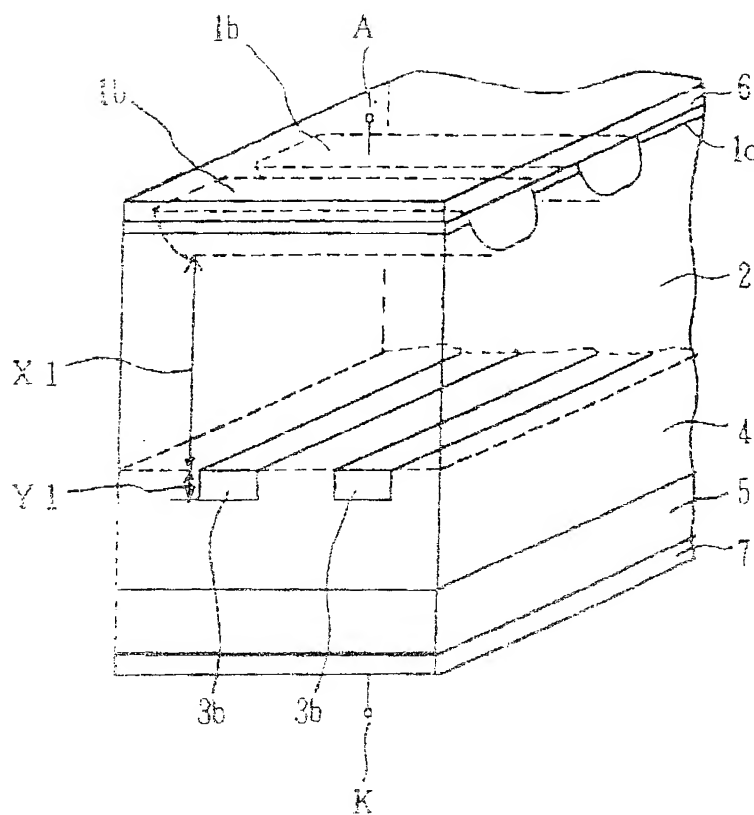




Fig. 24(a)

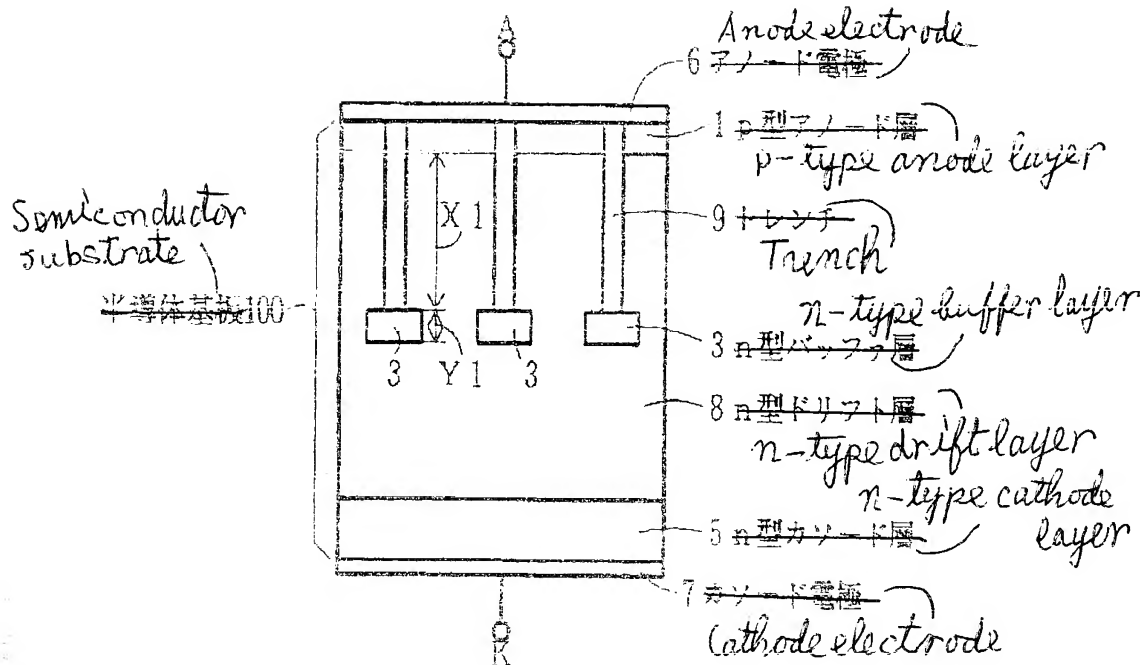


Fig. 24(b)

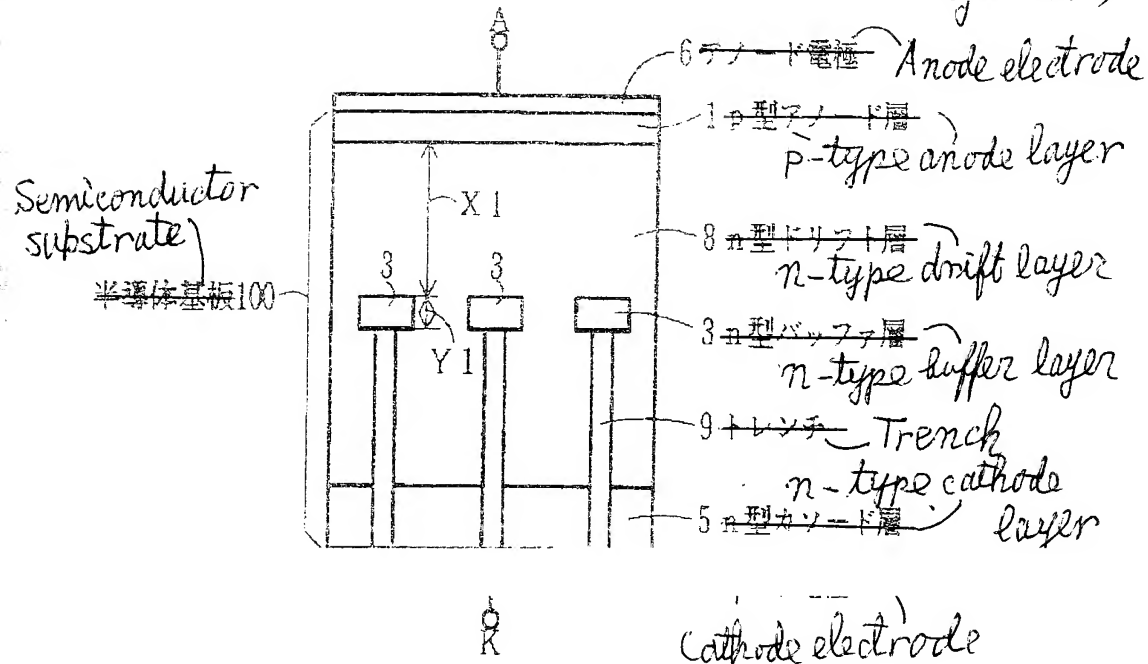


Fig. 25

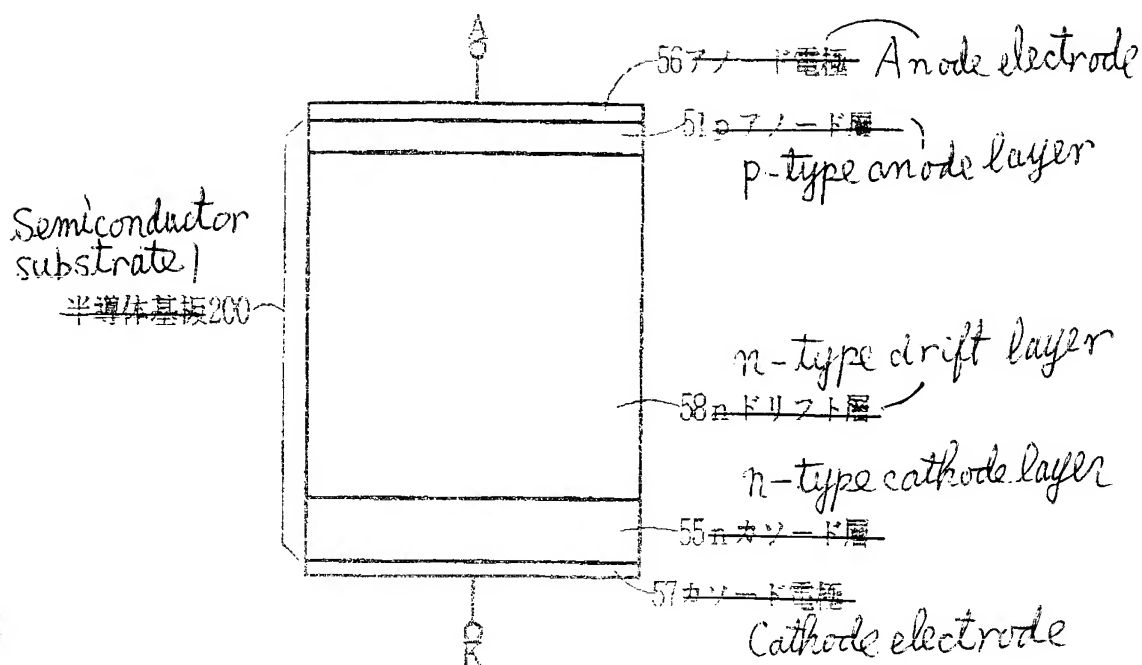


Fig. 26

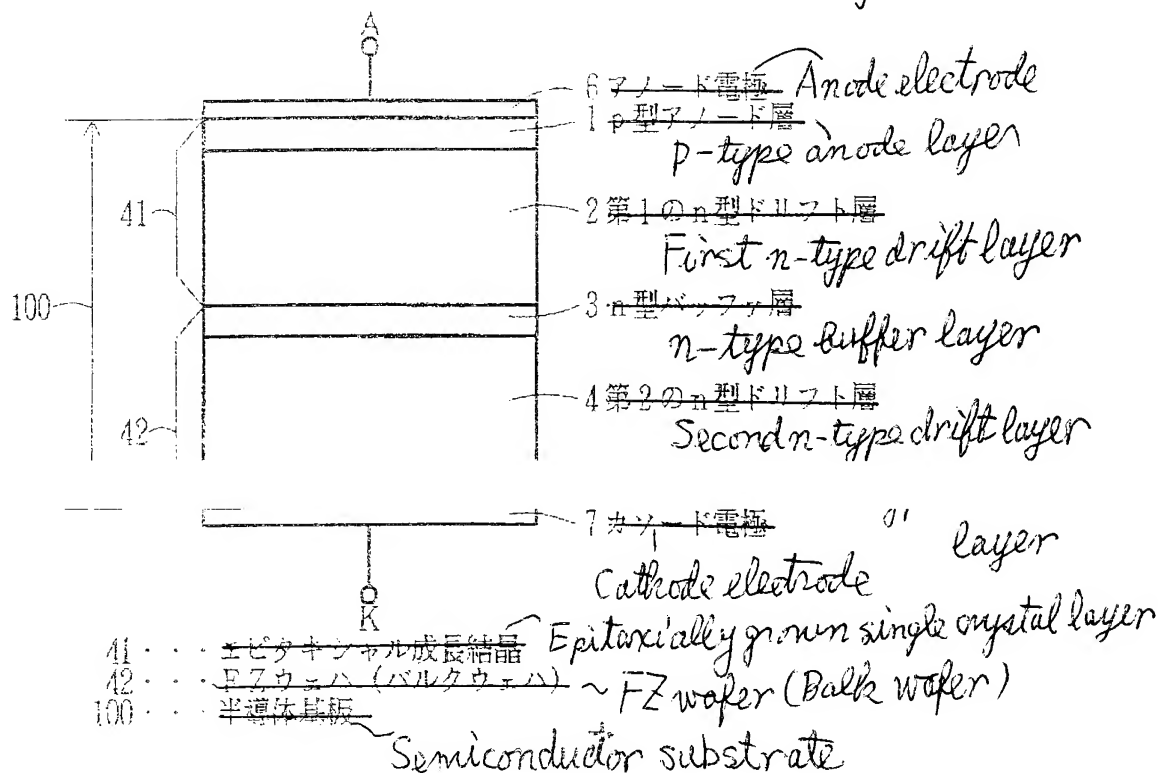


Fig. 27

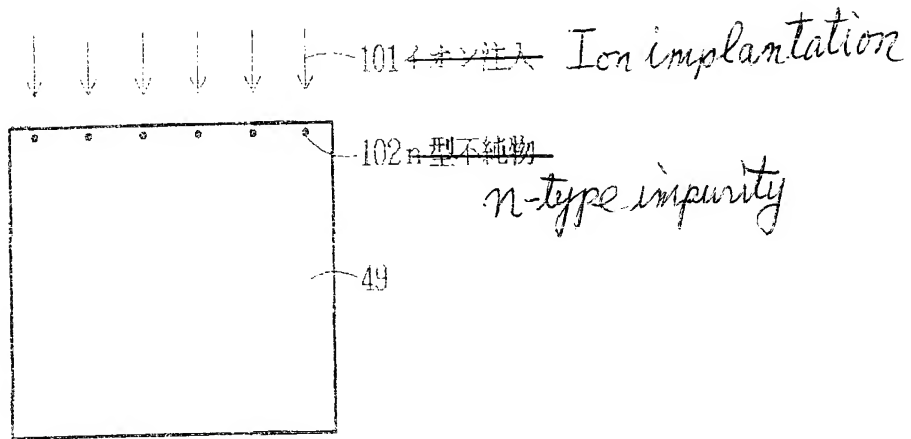


Fig. 28

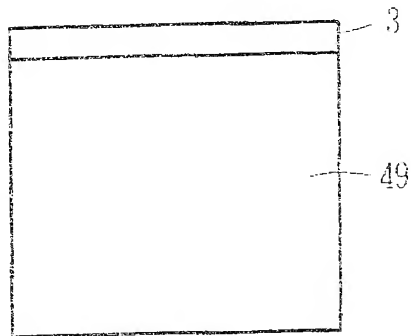


Fig. 29

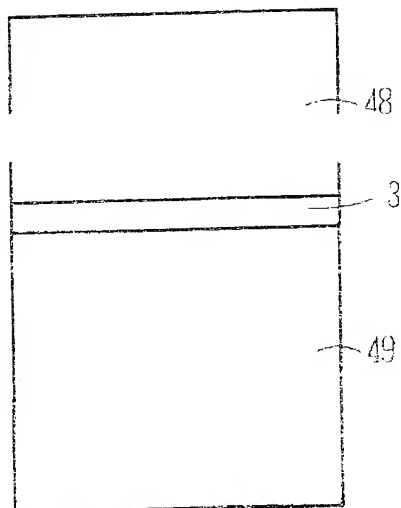


Fig. 30

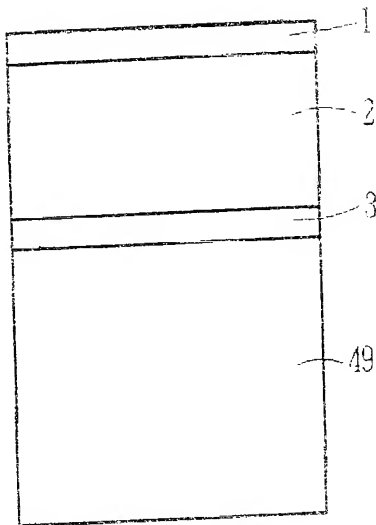


Fig. 31

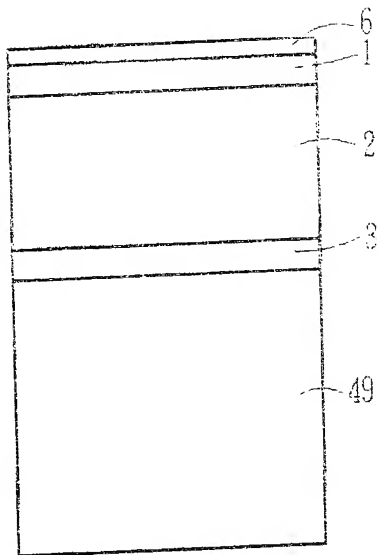


Fig. 32

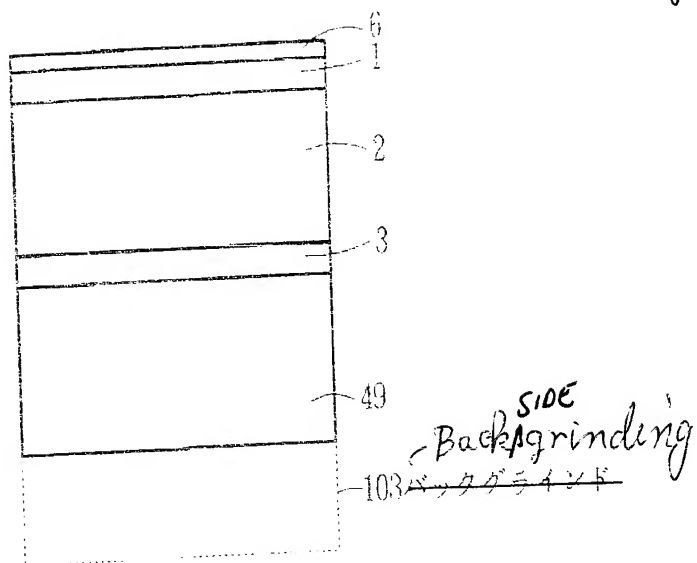
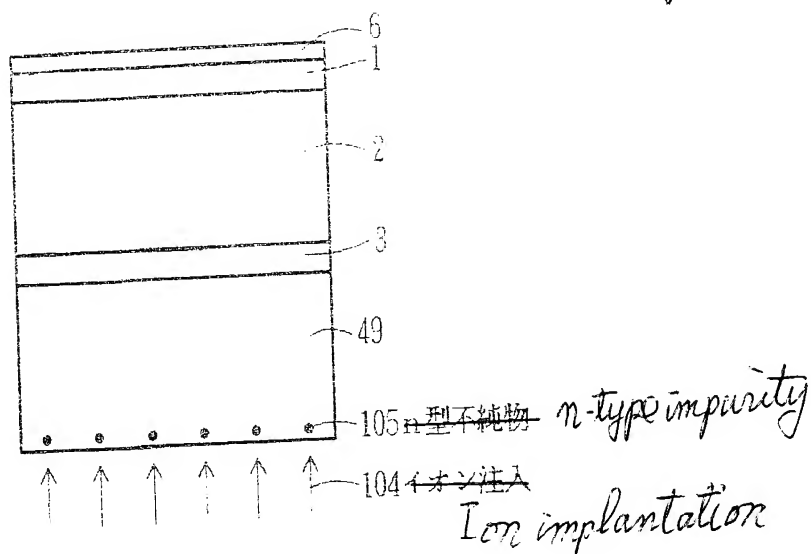


Fig. 33



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Fig. 34

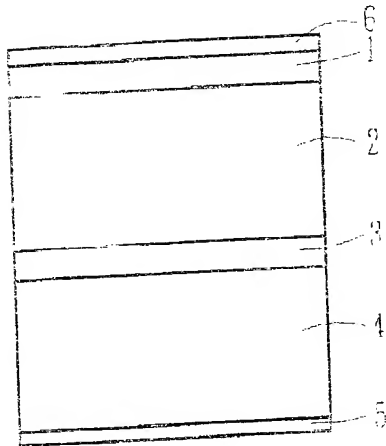


Fig. 35

